



FIG.1

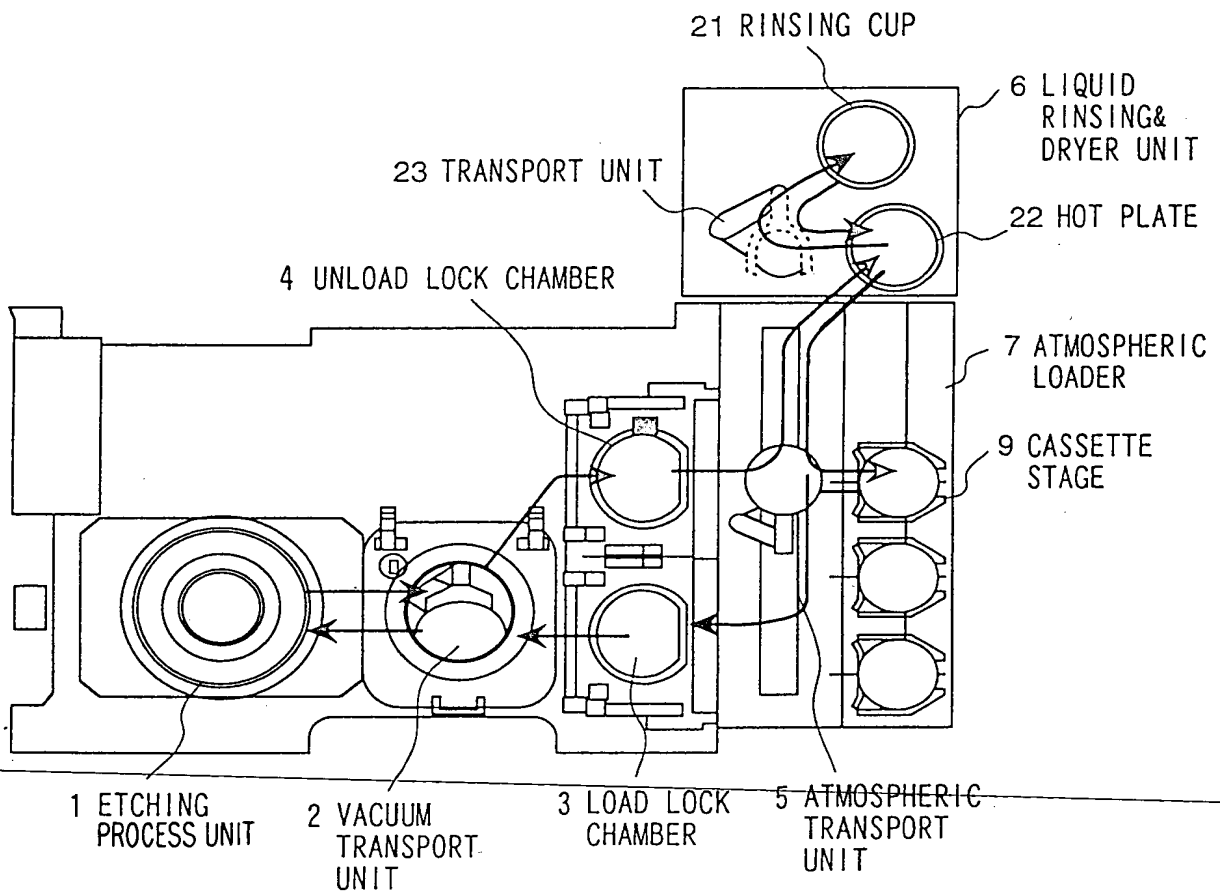


FIG.2

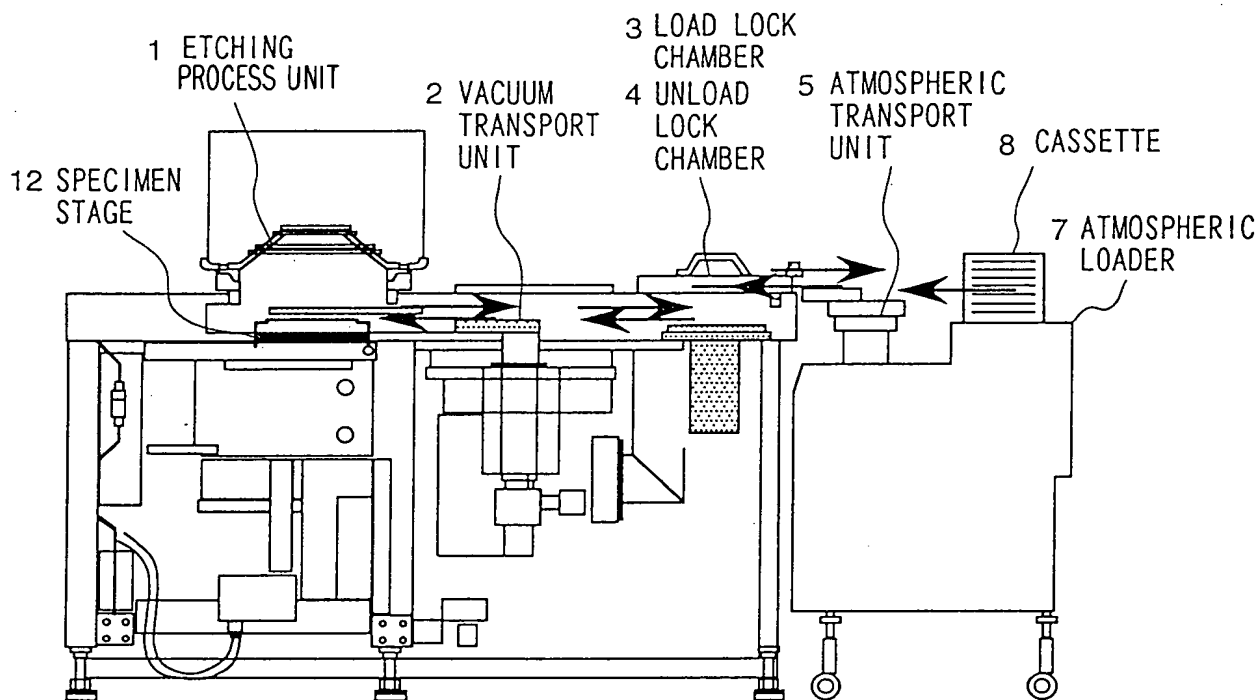
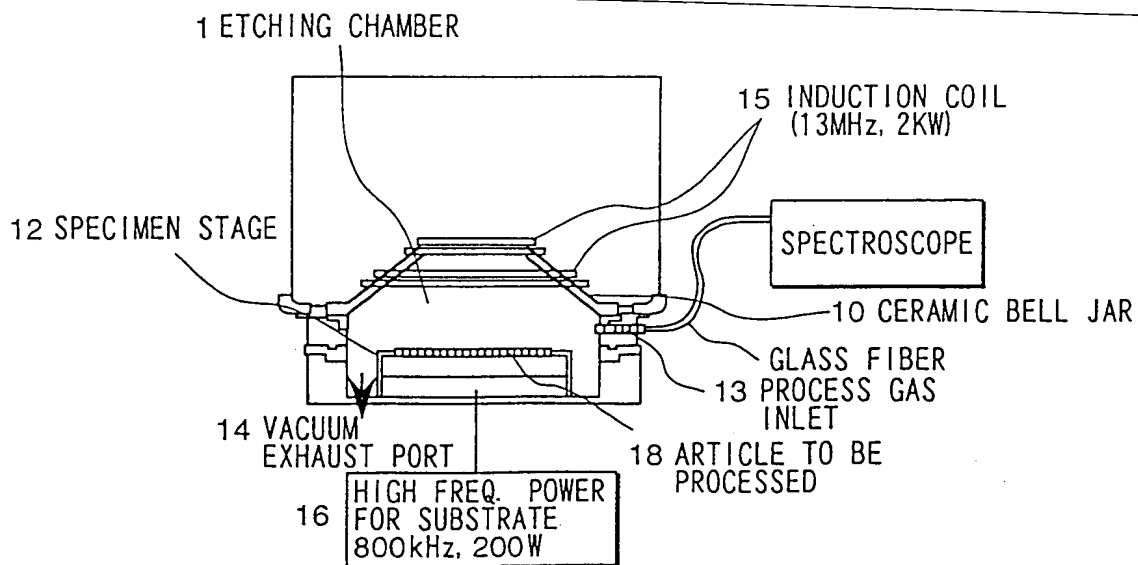


FIG.3





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FIG. 9

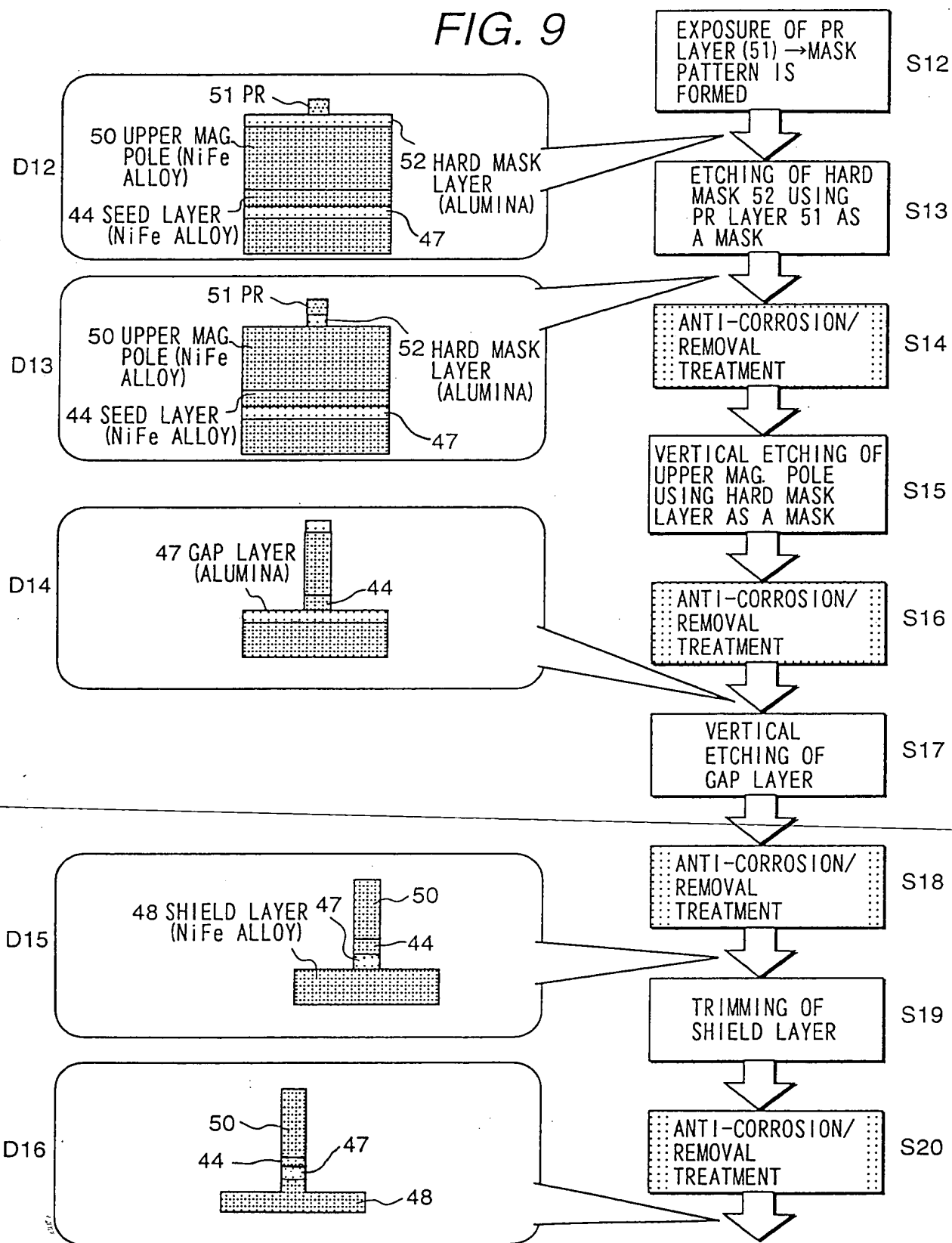




FIG.10

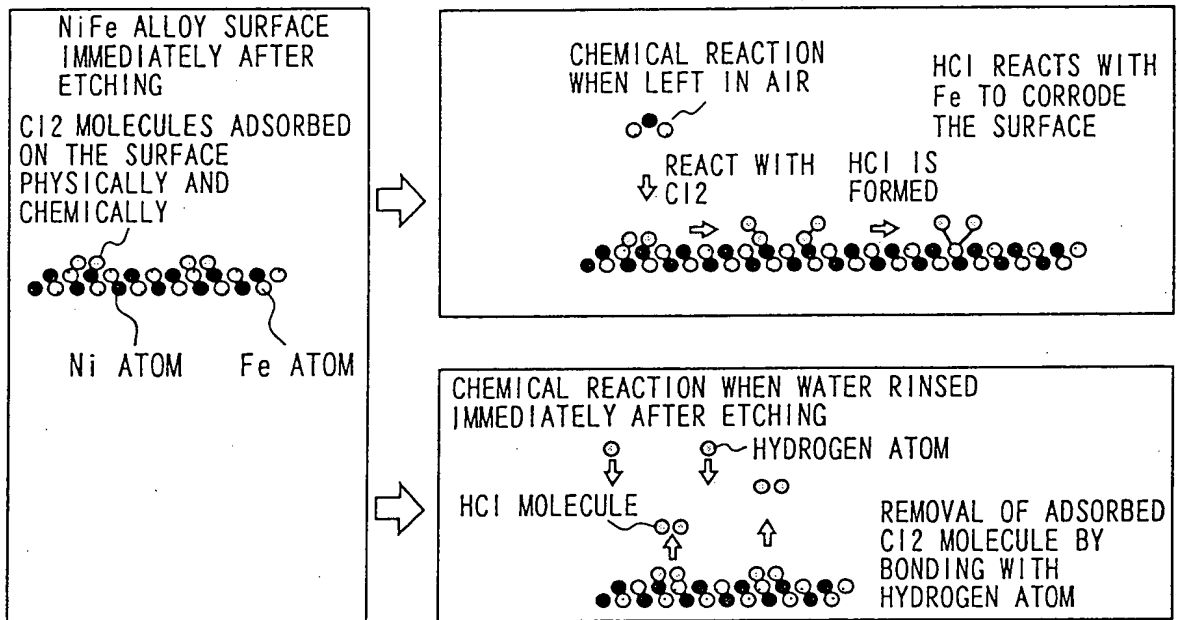
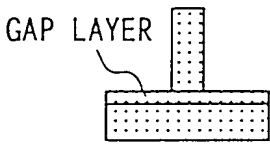
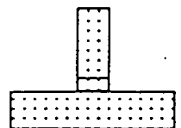
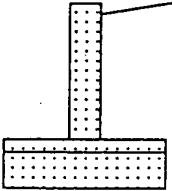
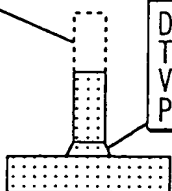


FIG.12

	BEFORE ETCHING	AFTER ETCHING
PLASMA ETCHING		
MILLING	 <p>A LONGER INITIAL LENGTH OF UPPER MAGNETIC POLE NECESSITATED DUE TO LOW SELECTIVITY RATIO → DIFFICULT TO OBTAIN PRECISE SIZE CONTROL</p>	 <p>DIFFICULT TO OBTAIN VERTICAL PATTERN</p>